

WRC-012 Datasheet

High-Precision Lift and Rotate Stage for Semiconductor Processing

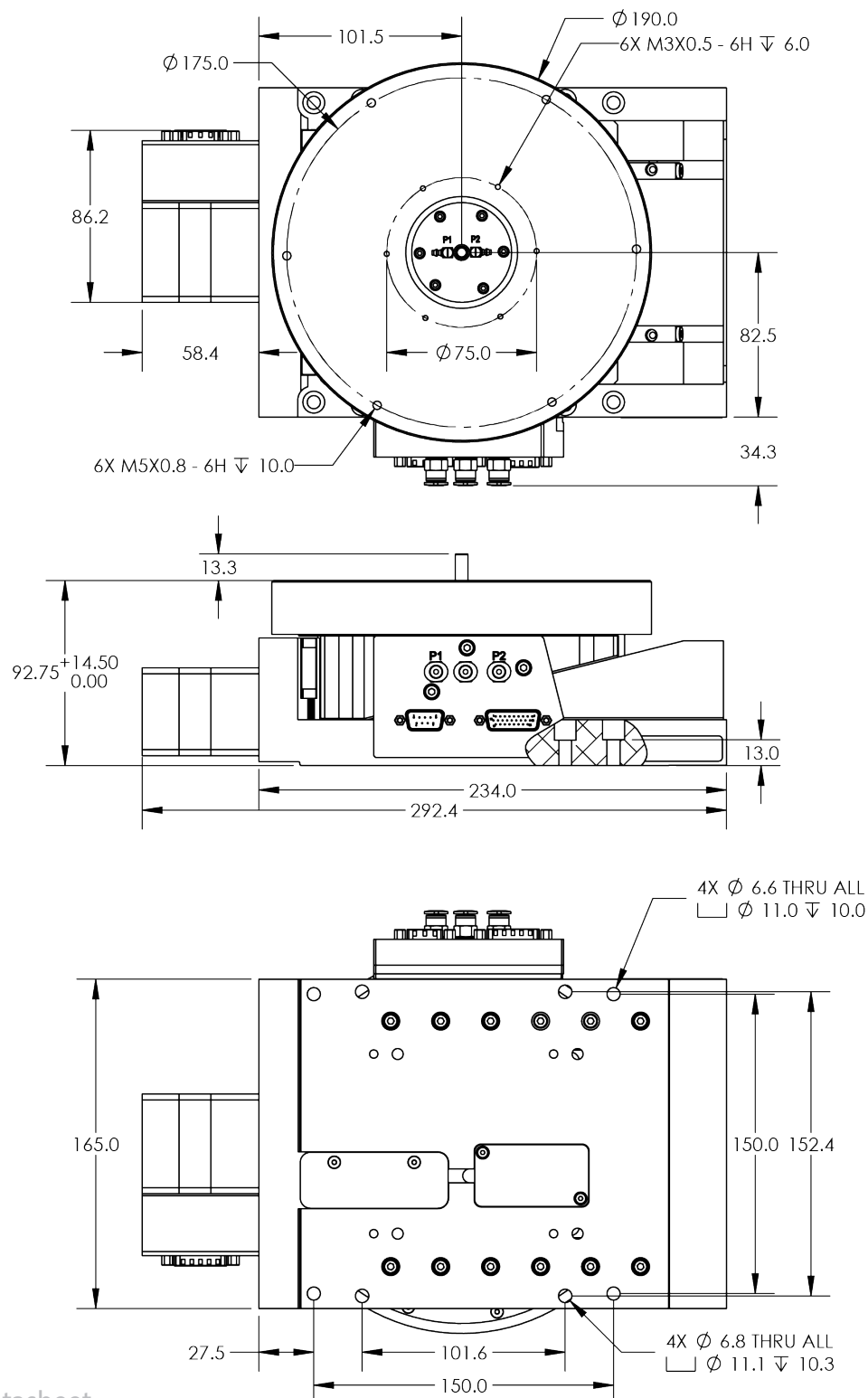
FEATURES

- 12.5mm of Vertical Travel
- Continuous Rotational Travel
- Optional Pneumatic Rotary Union for Wafer-Chucking
- Variety of Encoder Options
- Crossed Roller Linear Bearings
- Direct-Drive Rotary Motor
- Optional Cleanroom Compatibility



The WRC-012 is a high-precision vertical-lift and rotation stage engineered specifically for wafer-chuck manipulation in semiconductor processing. Combining a wedge-based lift mechanism with a smooth, direct-drive rotary axis, the WRC-012 provides accurate, repeatable positioning for demanding semiconductor applications. Its compact, stable design maintains precision under load, while the integrated lift-and-rotate architecture simplifies system design and reduces stack-up errors. Ideal for inspection, metrology, and general wafer handling, the WRC-012 delivers reliable, high-performance motion in cleanroom environments.

WRC-012 Dimensions



WRC-012 Ordering Options

WRC-012 Ordering Options	
Product Series	WRC: Z/Θ Stage for Semiconductor Wafers
Z Stage Travel	012: 12.5mm Between Limit Switches ¹
Rotary Axis Travel	360: Full 360° Rotation ²
Z Axis Feedback	H: RS422, Rotary Encoder, 32,000 counts/mm HH: 1Vpp Sin-Cos, Linear Encoder (50 sine periods/mm) M: RS422, Linear Encoder, 10,000 counts/mm
Rotary Axis Feedback	C: RS422, 1,800,000 counts/rev D: RS422, 7,200,000 counts/rev E: 1Vpp Sin-Cos (18,000 sine periods/rev)
Additional Options	0: No Additional Options M: 3-Channel Pneumatic Rotary Union (2 Positive, 1 Vacuum as Standard)
Customizations	00: Standard Product 01-99: Custom Stage, Customer Specific ³
Example Part Number	WRC-012-360-HH-E-M-02
Notes	1: Custom travels may be available below 12.5mm 2: Limit switches and hard stops may be added to limit the rotary axis to less than 360° 3: Common customizations include: custom hole patterns and cleanroom preparation



WRC-012 Performance Specifications

Performance Specifications		
Axis	Z	Θ
Accuracy ¹	$\pm 5 \mu\text{m}^3$	$\pm 30 \text{ arc-sec}$
Repeatability ¹	$1 \mu\text{m}^3$	3 arc-sec
Max Velocity	10 mm/s	See Table
Flatness (Y Movement) ²	10 μm	
Straightness (X Movement) ²		
Pitch ¹	10 arc-sec	
Yaw ¹		
Axial Runout ²		10 μm
Radial Runout ²		
Wobble ²		$\pm 15 \text{ arc-sec}$
Max Payload	20 kg	
Continuous Torque		1.56 Nm
Lifting Force	400 N	

Notes:
1: Specification is verified via laser interferometer on every stage
2: Specification may be verified upon request, additional charges may apply
3: Assumes linear encoder is equipped for Z Axis feedback

WRC-012 Maximum Rotational Velocity	
Encoder Feedback Code	Max Velocity ($^{\circ}/\text{s}$) ^{1,2}
C	1750
D	400
E	2650

Notes:
1: The true maximum velocity of a rotary stage is dependent on the controls system as well as the stage
2: Pneumatic air union option may limit max velocity below these values

